

ABSTRACT

HIGH PRESSURE SUBSTRATE PROCESSING APPARATUS

Provided is a high pressure substrate processing apparatus including: an inner chamber accommodating a substrate to be processed and a reaction gas supplied at a first pressure higher than an atmospheric pressure; an outer chamber including an external housing accommodating the inner chamber, and an external door movable between a closed state where the external housing is closed and an opened state where the external housing is opened, and accommodating a protective gas supplied at a second pressure set with respect to the first pressure; a fastening module configured to fasten the external housing with the external door in the closed state; and a capture module disposed to be adjacent to a contact position between the external housing and the external door for their fastening, and configured to capture a foreign material.

Fig. 2